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INVESTIGATION ON THE VACUUM PROPERTIES OF AL - TIZRV BI-LAYER FILMS

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Maintaining an ultra-high vacuum (UHV) environment is essential for the Hefei Advanced Light Facility (HALF) to achieve its design performance. Owing to the dimensional limitations imposed by small-aperture vac-uum chambers, non-evaporable getter (NEG) films are commonly applied to the inner walls to enhance vacuum performance. However, conventional NEG films increase the resistive-wall impedance of the vacuum pipes, there-by exacerbating the wakefield effects. To address this problem, a novel composite film, Al-TiZrV, has been developed. By covering the TiZrV film surface with a highly conductive film, it can reduce the resistivity of the composite film. The results show that while the addi-tion of the Al layer reduces the resistivity significantly, it increases the secondary electron yield (SEY), exacerbat-ing the electron cloud effect. This study provides insights into the complex properties of similar bilayer films for future research on accelerator-related materials.

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